	Hits	Search Text	DBs
60	91	(((resist or photoresist) near3 pattern$4) same (irradiat$4 or illuminat$4 or expos$4) same (remov$5 or eliminat$4) same (residu$5 or remain$5 or post$$develop$4) same (develop$5 or TMAH)) and ((ultraviolet or UV or VUV or EUV or X$2ray or DUV) near9 (laser or ablat$4 or irradiat$4 or illuminat$4 or expos$4) near12 (resist or photoresist) near10 (remain$3 or residu$5) near19 develop$5)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
61	91	(((resist or photoresist) near3 pattern$4) same (irradiat$4 or illuminat$4 or expos$4) same (remov$5 or eliminat$4) same (residu$5 or remain$5 or post$5develop$4) same (develop$5 or TMAH)) and ((ultraviolet or UV or VUV or EUV or X$2ray or DUV) near9 (laser or ablat$4 or irradiat$4 or illuminat$4 or expos$4) near12 (resist or photoresist) near10 (remain$3 or residu$5) near19 develop$5)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
62	114	(((resist or photoresist) near3 pattern$4) same (irradiat$4 or illuminat$4 or expos$4) same (remov$5 or eliminat$4) same (residu$5 or remain$5 or post$5develop$4) same (develop$5 or TMAH)) and ((ultraviolet or UV or VUV or EUV or X$2ray or DUV) near16 (laser or ablat$4 or irradiat$4 or illuminat$4 or expos$4) near12 (resist or photoresist) near5 (remain$3 or residu$5 or unexposed) near19 develop$5)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
63	68	(((resist or photoresist) near3 pattern$4) same (irradiat$4 or illuminat$4 or expos$4) same (remov$5 or eliminat$4) same (residu$5 or remain$5 or post$5develop$4) same (develop$5 or TMAH)) and ((ultraviolet or UV or VUV or EUV or X$2ray or DUV) near16 (laser or ablat$4 or irradiat$4 or illuminat$4 or expos$4) near12 (resist or photoresist) near5 (remain$3 or residu$5 or unexposed) near19 develop$5) and strip$4	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB